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APPLICATION NO.	FI	LING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09/688,989	10/17/2000		Yoshitaka TSUNASHIMA	04329.1952-01000 2408	
22852	7590	07/14/2006		EXAMINER	
FINNEGA	N, HEND	ERSON, FARABO	RAO, SHRINIVAS H		
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Please find below and/or attached an Office communication concerning this application or proceeding.

<u>.</u>	Application No.	Applicant(s)
	09/688,989	TSUNASHIMA ET AL.
Office Action Summary	Examiner	Art Unit
	Steven H. Rao	2814
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	correspondence address
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING D. - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period of Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tin will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).
Status		
1) ☐ Responsive to communication(s) filed on 23 M 2a) ☐ This action is FINAL. 2b) ☐ This 3) ☐ Since this application is in condition for alloware closed in accordance with the practice under E	s action is non-final. nce except for formal matters, pro	
Disposition of Claims		
4) Claim(s) 27,28 and 30-34 is/are pending in the 4a) Of the above claim(s) is/are withdrays 5) Claim(s) is/are allowed. 6) Claim(s) 27-28, 30-34 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or are subject to restriction and/or are subjected to by the Examine 10) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) accomplicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Examine 11) The oath or declaration is objected to by the Examine 11) The oath or declaration is objected to by the Examine 11)	wn from consideration. or election requirement. er. epted or b) objected to by the drawing(s) be held in abeyance. Settion is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	ts have been received. Is have been received in Application of the process of th	ion No ed in this National Stage
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal F 6) Other:	

DETAILED ACTION

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on May 19, 2006 has been entered on May 23, 2006.

Priority

The parent Application No. 09/688,989 filed on June 29, 1998 claims priority from Japanese Patent Application Nos. 9-17205(6/30/1997) 10-042056(2/24/1998) and 10-195453(6/30/1998).

Preliminary Amendment

Applicants' amendment filed on March 21, 2006 has been entered on May 23, 2006.

Therefore claim 27 as amended by the amendment and claims 28 and 30-34 as previously recited are currently pending in the Application.

Claims 1-26 and 29 have been cancelled.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action: (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the

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prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 27-28 and 30 to 34 rejected under 35 U.S.C. 103(a) as being unpatentable over De LA Moneda et al. (U.S. Patent No. 4,45, 267, herein after De La Moneda, previously applied) and further in view of AAPR (Applicants' Admitted Prior Art shown at least in figs. 1- 3F and describes in the specification at page 6 lines 1-17 etc.).

With respect to claim 27 De La Moneda describes a semiconductor device comprising: a semiconductor substrate including a first and second region separated by an isolation element, (De La Moneda figs. 1-1 # lo-substrate, figs. #12 isolation element col. 4 lines 20-25 etc.) a first transistor formed on the first region of the substrate (claim 7, col. 6 lines 35-40) and including a first insulation film (figs. # 16, and including a second insulation film and a second gate electrode arranged along the first direction, (figs. Structure above 18) wherein a side wall of the first gate electrode is connected to a side wall of the second gate electrode above the isolation element when viewed from a direction perpendicular to the first direction. (fig 10 # 42 connecting over isolation element 12).

De La Moneda does not specifically mention the presently newly added limitation of "the sidewall of the first gate electrode is directly physically and with out the presence of additional layers there between ".

However AAPR in at least figures 1 to 3 E and the description in page 6 lines 117 shows and describes both physical and electrical direct connection between element
16 and first and second gates including their sidewalls to provide a method that uses
conventional processing steps to form a junction between adjacent electrodes. This in
turn saves valuable real estate by reducing number on inter level connections required
and thus uses less number of steps to form the device.

Therefore it would have been obvious to one of ordinary skill in the art at the time of the invention to include AAPR's the sidewall of the first gate electrode is directly physically and with out the presence of additional layers there between In De LA Moneda's device. The motivation to make the above combination (as is known to one of ordinary skill in the art) is to provide a method that uses conventional processing steps to form a junction between adjacent electrodes. This in turn saves valuable real estate by reducing number on inter level connections required and thus uses less number of steps to form the device.

With respect to claim 28, De La Moneda describes a device according to claim 33, wherein a side of the side insulator film is on a surface of said semiconductor. (De La Moneda figures e.g. fig. 10 #38, col. 12-16).

With respect to claim 30 De La Moneda describes a device according to claim 28, wherein at least one of said first and second gate electrodes is formed by a damascene gate process.. (De La Moneda figures 1-11, same as Applicants' description at least at page 9 lines 10-25 and page 26 lines 2 to 20 for their gate formation).

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With respect to claim 31 De La Moneda describes a device according to claim 33, wherein said first insulation film is thinner than said second insulation film, said first transistor forms a logic circuit, and said second transistor forms a memory cell. (De La Moneda figures, col.2 lines 30-36).

With respect to claim 32 De La Moneda describes a device according to claim 33, wherein top surfaces of said first and second gate electrodes are coplanar. (De La Moneda figures).

With respect to claim 33 De La Moneda describes a device according to claim 27, wherein said second transistor further comprises a polysilicon layer formed on the second insulation film formed on the substrate, (De La Moneda figure 10 # 20 over 16) and a side insulator film formed ùn a side of the second insulation film and a side wall of the polysilicon layer, (De La Moneda figure 10 # 38) said second gate electrode is formed on the polysilicon layer, (De La Moneda figure 10) and connected to the side wall of the second insulation film and the side wall of the polysilicon layer via the side insulator film substrate. (De La Moneda figures specifically 10 and col. 6.,7).

With respect to claim 34 De La Modena describes a device to claim 27, wherein the side wall of the first gate electrode is directly connected to the side wall of the second gate electrode. (De La Modena figure 10 and see also Applicants' admitted prior art at least in figures 1-3E and the description at least page 6 lines 1-17 (especially 9-17).

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Applicant's arguments filed on May 23, 2006 have been fully considered but they are most in view of new rejection.

Response to Arguments

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Steven H. Rao whose telephone number is (571)272-1718. The examiner can normally be reached on 8.00 to 5.00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Fahmy Wael can be reached on (571) 272-1714. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Steven H. Rao

Patent Examiner

July Q6, 2006

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